Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L6	5860	((etch$3 or remov$3) same (porous near silicon or "Si")) same (hydrogen near fluoride or hydrofluoric near acid or "HF")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:02
L7	463	6 same (vapor$4 same etch$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:22
L8	130	7 same temperature	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:23
L9	85	8 and @pd<"20030120"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:03
L10	664	((etch$3 or remov$3) same (porous near silicon)) same (hydrogen near fluoride or hydrofluoric near acid or "HF")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:44
L11	9	10 same (vapor$4 near etch$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:51
L12	17	10 and (vapor$4 near etch$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:51
L13	7	12 and (peroxide or "H.sub.2 O. sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:51
L14	198	((etch$3 or remov$3) same (porous near silicon) same (silicon near "2" oxide)) same (hydrogen near fluoride or hydrofluoric near acid or "HF")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:12

L15	142	14 and @pd<"20030120"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:04
L16	42	15 and (hydrogen near peroxide or "H.sub.2 O.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:05
L17	31	16 and vapor$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:06
L18	145	((etch$3 or remov$3) same (porous near silicon)) same vapor$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:13
L19	100	18 and (hydrogen near fluoride or hydrofluoric near acid or "HF")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:14
L20	23	19 and (hydrogen near peroxide or "H.sub.2 O.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:14
S1	2	("5423944").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/14 10:57
S2	7	(("20010044216") or ("6380099") or ("6,127,281") or ("6,254,794") or ("5,767,020") or ("6,171,512") or ("6,238,586")).PN.	US-PGPUB; USPAT	OR	OFF	2005/09/14 12:10
S3	38233	((vapor$4 or heat$3) same etch$3) same silicon	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/14 12:51
S4	7475	S3 and (porous or (ion near implant$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/14 12:12

S5	675	S4 and (temperature same degree)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/14 12:13
S6	400	S5 and @pd<"20030120"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/14 12:52
S7	280	((vapor$4 or heat$3) same etch$3) same (porous near silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/14 12:52
S8	180	S7 and @pd<"20030120"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/14 12:52
S9	203	S7 and (hydrofluoric near acid or "HF" or hydrogen near fluoride)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/14 12:53
S10	69	S9 and (peroxide or "H.sub.2 O. sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/14 12:57
S11	68	S10 and temperature	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/14 12:58

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L6	5860	((etch$3 or remov$3) same (porous near silicon or "Si")) same (hydrogen near fluoride or hydrofluoric near acid or "HF")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:02
L7	463	6 same (vapor$4 same etch$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:22
L8	130	7 same temperature	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:23
L9	85	8 and @pd<"20030120"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:03
L10	664	((etch$3 or remov$3) same (porous near silicon)) same (hydrogen near fluoride or hydrofluoric near acid or "HF")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:44
L11	9	10 same (vapor$4 near etch$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:51
L12	17	10 and (vapor$4 near etch$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:51
L13	7	12 and (peroxide or "H.sub.2 O.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 06:51
L14	198	((etch$3 or remov$3) same (porous near silicon) same (silicon near "2" oxide)) same (hydrogen near fluoride or hydrofluoric near acid or "HF")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:12

L15	142	14 and @pd<"20030120"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:04
L16	42	15 and (hydrogen near peroxide or "H.sub.2 O.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:05
L17	31	16 and vapor$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:06
L18	145	((etch$3 or remov$3) same (porous near silicon)) same vapor$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:13
L19	100	18 and (hydrogen near fluoride or hydrofluoric near acid or "HF")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:40
L20	23	19 and (hydrogen near peroxide or "H.sub.2 O.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:14
L21	57701	(gas$4 or dry or vapor$4) same (etch$3 same silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:39
L22	851	21 same (porous)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:40
L23	90	22 and ((hydrogen near fluoride or hydrofluoric near acid or "HF") same (hydrogen near peroxide or "H.sub.2 O.sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/15 07:58
L24	5	takanashi-kazuhito.in.	US-PGPUB; USPAT	OR	OFF	2005/09/15 07:59
L25	55	yamagata-kenji.in.	US-PGPUB; USPAT	OR	OFF	2005/09/15 08:00

| L26 | 9 | 25 and (vapor$4 same ((porous near silicon) or (porous near "Si"))) | US-PGPUB; USPAT | OR | OFF | 2005/09/15 08:00 |